

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	77	("20020020821" "20020109823" "20020163629" "20030123040" "20030174408" "20040000627" "20040021844" "20040075895" "20040109237" "20040119954" "20040125351" "20050259234" "20050264774" "3573975" "3648587" "4346164" "4390273" "4396705" "4480910" "4509852" "5040020" "5121256" "5610683" "5715039" "5825043" "5900354" "6191429" "6236634" "6560032" "6600547" "6603130" "6633365" "6665046" "6781668" "6788477" "6809794" "6867844").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 16:42
L2	1063	(\$4lithograph\$4 or exposure) and (substrate or wafer) and (reticle or mask or pattern\$4) and (projection adj3 (optical or lens or system or device or apparatus)) and ((liquid or solution or fluid or water) adj3 (supply\$4 or provid\$4 or inlet))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 16:56
L3	137	2 and (((liquid or solution or fluid or water) near4 (supply\$4 or provid\$4)) near4 (apparatus or system or device or inlet)) same ((barrier or seal\$4) adj3 (member or plate or element)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 16:50
L4	4	3 and (((outlet or discharg\$4 or remov\$4 or recover\$4) near4 (liquid or solution or fluid or water)) near6 (radial\$4 near4 outward\$43) near5 (barrier))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 16:53
L5	1	(((\$4lithograph\$4 or exposure) and (substrate or wafer) and (reticle or mask or pattern\$4) and (projection adj3 (optical or lens or system or device or apparatus)) and ((liquid or solution or fluid or water) adj3 (supply\$4 or provid\$4 or inlet)) and (((outlet or discharg\$4 or remov\$4 or recover\$4) near4 (liquid or solution or fluid or water)) near6 (radial\$4 near4 outward\$43) near5 (barrier))))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 17:00

## EAST Search History

L6	7	(((\$4lithograph\$4 or exposure) and (substrate or wafer) and (reticle or mask or pattern\$4) and (projection adj3 (optical or lens or system or device or apparatus)) and (((liquid or solution or fluid or water) adj3 (supply\$4 or provid\$4 or inlet)) and (((outlet or discharg\$4 or remov\$4 or recover\$4) near4 (liquid or solution or fluid or water)) near6 (radial\$4 near4 outward\$43) near5 (inlet or suppl\$4 or provid\$4))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 17:05
L7	0	(((\$4lithograph\$4 or exposure) and (substrate or wafer) and (reticle or mask or pattern\$4) and (projection adj3 (optical or lens or system or device or apparatus)) and (((liquid or solution or fluid or water) adj3 (supply\$4 or provid\$4 or inlet)) near5 (vibration\$4 or mechanism\$4) near4 (isolat\$4)) and (((outlet or discharg\$4 or remov\$4 or recover\$4) near4 (liquid or solution or fluid or water)) near6 (radial\$4 near4 outward\$43) near5 (inlet or suppl\$4 or provid\$4))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/06 17:06